CITY OF ELKHART, INDIANA INDUSTRIAL WASTE QUESTIONNAIRE

SEC	TION A. <u>GENERAL INFORMATION</u> (Type or Print, Please)
l .	Company Name Elkhart Products Corporation
2.	Mailing Address 1255 Oak Street, POB 1008
3.	Address of Premises 1255 Oak Street, Elkhart, IN 46515
.	Name and Title of Signing Official Cliff Cartwright, Corporate Plant Eng
5.	Wastewater discharges to:
	City sewer system X
	Private septic system
5 .	If your facility discharges to the City sewer system, check the types of discharges:
	X Sanitary Wash water X Rinse water
	Cooling water X Process water Scrubber water
	Other
	Note: If your facility discharges only to a private septic system and not to the City sewer system, or if only sanitary sewage is discharged to the City sewer system, it is only necessary to fill out Section A of this questionnaire. Otherwise, complete entire questionnaire.
7.	Contact Official
	Name Cliff Cartwright
	Title Corporate Plant Engineer
	Address 1255 Oak Street, POB 1008, Elkhart, IN 46515
	Phone Number (219) 264-3181
	The information contained in this questionnaire is familiar to me and to the best of my knowledge and belief, such information is true, complete, and accurate.
	Date Signature of Official
	. The second of \mathcal{C}

SEC	TION B. PRODUCT OR SERVICE INFORMATION
1.	Brief description of manufacturing or service activity on premises:
	Manufacturing wrot copper fittings and drainage solder-joint
	fittings. Also, extrude and bend aluminum tubing.
2.	Principal Raw Materials Used:
	Copper tubing and aluminum tubing.
3.	Catalysts, Intermediates:
	See Section F.
4.	Principal Product or Service (use Standard Industrial Classification
	Manual if appropriate): Rolling, drawing and extrusion of copper
	(SIC 3351) and aluminum extended products (SIC 3354).
5.	Appended to this questionnaire is a list of Standard Industrial Classification (SIC) codes for industries currently or potentially subject to USEPA preteatment regulations. List SIC codes for each of your processes that are subject to USEPA pretreatment

regulations.

sic 3351, sic 3354

SEC	ON C. PLANT OPERATIONAL CHARACTERISTICS
1.	ype of Discharge: Batch X Continuous Both
	or batch discharges, list types, average number of batches/24 hrs
	and volume (gallons) per batch.
2.	s there a scheduled shutdown? No
	Then?
3.	s production seasonal? No
	f yes, explain indicating months(s) of peak production.
4.	everage number of employees per shift: 169 lst; 68 2nd; 29 3rd
5.	Shift start times: 6:48 AM 1st; 4:30 PM 2nd; 11:00 PM 3rd
6.	Shifts normally worked each day of the week:
	Sun Mon Tue Wed Thu Fri Sat
	st <u>X X X X X</u>
	2nd X X X X X
	ard X X X X
7.	Describe any wastewater treatment equipment or processes in use: We currently neutralize the discharge from our roto-finish
	cleaning operation to achieve proper ph.

SECTION D. WATER CONSUMPTION AND LOSS

1. Raw Water Sources:											
<u>Source</u>			Quantity								
City water			11,000	_ gallon	s per	day					
8" well			51,000	_ gallon	s per	day					
10" well (not in	service)		*	_ gallon	s per	day					
			 	_ gallon	s per	day					
2. Water treatment pr	ocesses in	use:									
Chemical c	oagulation, etc.	including	use of al	um, ferri	c chlo	oride					
X Lime softe	ning										
Resin (ion	Resin (ion exchange) water softening										
Filtration	Filtration										
Chemical (chlorine or	ozone) dis	sinfection	ı							
Others Us	se of sulph	uric acid a	and sodium	n hydroxi	de to	<u> </u>					
a	chieve neut	ralization.									
3. List Water Consump	tion in Pla	nt:									
Cooling Water		3,6	5 <u>75</u> g	gallons p	er da	ıy					
Boiler Feed		·	329 8	gallons p	er da	ıy					
Process Water		55,3	336	gallons p	er da	ıy					
Sanitary System	1*	2,6	<u> </u>	gallons p	er da	ıy					
Contained in Pr	oduct		<u>)-</u> {	gallons p	er da	ıy					
Other ()) <u> </u>	gallons p	er da	ıy					
*Sanitary flow	can be esti	mated at 10) gpd per	employee	٠.						

Waste Hauler gallons per day Evaporation 7,000 gallons per day Contained in Product gallons per day Discharge to Sewer: Intermittent X Steady t average water usage for SIC Processes itemized in Section above: ulated Average Water C No Brief Process Description Consumption(GPD)	City Was	stewater Sewer	45,000	gallons per day
Waste Hauler gallons per day Evaporation 7,000 gallons per day Contained in Product gallons per day Discharge to Sewer: Intermittent X Steady st average water usage for SIC Processes itemized in Section above: Gulated Average Water C No Brief Process Description Consumption(GPD)	Septic :	Tank Discharge		gallons per day
Contained in Product gallons per day Discharge to Sewer: Intermittent X Steady st average water usage for SIC Processes itemized in Section above: Gulated Average Water Consumption(GPD)	Surface	Discharge	10,000	gallons perday
Contained in Product gallons per day Discharge to Sewer: Intermittent X Steady st average water usage for SIC Processes itemized in Section 5 above: gulated Average Water IC No Brief Process Description Consumption(GPD)	Waste Ha	auler		gallons per day
S Discharge to Sewer: Intermittent X Steady ist average water usage for SIC Processes itemized in Section -5 above: egulated	Evapora	tion	7,000	gallons per day
ist average water usage for SIC Processes itemized in Section -5 above: egulated SIC No. Brief Process Description Consumption(GPD)	Contain	ed in Product		gallons per day •
3351 Cleaning & polishing of copper products. 6,000	List avera B-5 above:	age water usage for	SIC Processes	itemized in Section
	List avera B-5 above: Regulated	age water usage for	SIC Processes	itemized in Section Average Water
	List avera 3-5 above: Regulated SIC No.	age water usage for Brief Process D	SIC Processes	itemized in Section Average Water Consumption(GPD)
	List avera 3-5 above: Regulated SIC No.	age water usage for Brief Process D	SIC Processes	itemized in Section Average Water Consumption(GPD)
	List avera B-5 above: Regulated SIC No.	age water usage for Brief Process D	SIC Processes	itemized in Section Average Water Consumption(GPD)

SECTION E. SEWER CONNECTION AND DISCHARGE INFORMATION

1. List plant sewer outlets and flow: (assign sequential reference number to each sewer starting with No. 1).

Reference No.	Descriptive Location of Sewer Connection or Discharge Point	Avg. Flow (gpd)
1	N.E. side of plant/flow from restrooms and	4,000
	floor drain.	
2	N.E. side of plant/flow from roof and floor	1,000
•	drains.	
3	East side of plant/flow from sinks	1,500
	S.E. side of plant/flow from cold header sump (mild alkaline cleaner)	1,000
5	S.E. side of plant/flow from roto-finish cleaning operation (mild citric acid cleaner)	10,000
6	S.E. corner of property/flow from soaping line (soap used for lubricant)	27,500

- 2. Attach a scaled drawing or dimensioned sketch of the industrial complex showing location of sewer referenced in E-l above and location of the SIC process described in Section D-5. Show location of monitoring manhole, if any, and other possible sampling points for sewers and SIC process effluents. Indicate how City industrial monitoring staff can gain access to the sampling points. For reference and field orientation buildings, streets, alleys, and other pertinent physical structures should be included.
- 3. Is plant required to prepare a Spill Prevention Control and Countermeasure (SPCC) Plan per 40 CFR 112 or a RCRA Contingency Plan?
 Yes If report has been prepared, attach copy. Copy attached.
 Yes If report is required, but has not yet been prepared, indicate date when it will be submitted.

SECTION F. PRIORITY POLLUTANT INFORMATION

1. Please indicate by placing an "X" in the appropriate box by each listed chemical whether it is Suspected to be Absent, Known to be Absent, Suspected to be Present, or Known to be Present in your manufacturing or service activity or generated as a byproduct. Some compounds are known by other names. Please refer to Appendix A for those compounds which have an asterisk(*).

ITEM NO.	CHEMICAL COMPOUND	SUSPECTED	KNOWN	SUSPECTED PRESENT	KNOWN PRESENT	ITEM NO.	CHEMICAL COMPOUND	SUSPECTED ABSENT KNOWN	ABSENT	PRESENT	KNOWN
1.	ammonia		X			47.	chlorobenzene	2	ζ		
2.	asbestos (fibrous)		X			48.	chloroethane*)			
5.	cyanide (total)		X			49.	2-chloroethylvinyl ether	1 1		يصنيها	
						50.	chloroform"	1			
1.	antimony (total)		X		-	51.	chloromethane*				
5.	arsenic (total)		X			52.	2-chloronaphthalene		(
5.	beryllium (total)		X	-		53.	2-chlorophenol*		(
_ =:	cadmium (total)				X	54.	4-chloropnenylphenyl cher	1	({
3.	chromium (total)		 	 	X	55.	chrysene*		K		
9.	copper (total)			 	X	56.	4,4'-000*	1			-
10.	lead (total)		\top	T	X	57.	4,4'-DDE*		X		
11.	mercury (total)		X	1		58.	4,4'-DOT*		X		-
12.	nickel (total)			T	X	59.	dibenzo(a,h)anthracene*		χ.		
15.	selenium (total)		X	T	,	60.	dibromochloromethane*	i	X		
14.	silver (total)		X	1	t	61.	1,2-dichlorobenzene*		X		!
15.	thallium (total)				i	62.	11.3-dichlorobenzene"		X		T
16.	zinc (total)		-	 	X	63.	1,4-dichlorobenzene*		X		
				 	1	64.	3,3'-dichlorobenzidine		X		1
Ţ	acenapi:thene		X	+	i	65.	dichlorodifluoromethane*		X		
13.	acenaphthylene		X	T-	† 	66.	1,1-dichloroetname*		X		
19.	lacrolein		X	T	7	67.	1,2-dichloroethane*		X		
20.	acrylonitrile		X	1	T	68.	1.1-dichloroethene"		X		
21.	aldrin		X	i	7	69.	trans-1,2-dichloroethene	1	X		1
22.	anthracene		X	1	T	70.	2,4-dichlorophenol		X		-
23.	benzene		X	1	-	-1.	1,2-dichloropropane*	1 :	X		+
24.	benzidine		X	1		72.	(cis & trans)1,3-dichlo-				
25.	benzo(a)anthracene*		X	_	1		ropropene *	;	X		
26.	benzo(a)pyrene*		TX		Ť	73.	dieldrin		X		T
2-	benzo(b)fluoranthene		X)	74.	diethyl phthalate		X		T
28.	benzo(g,h,i)perylene*		X	1		1 -5.	2,4-dimethylphenol*		X		
29.	benzo(k)fluoranthene"		X		-	76.	dimethyl onthalate		X	 	1
30.	a-BHC (alpha)		X	1		T == .	di-n-butvl phthalate		X	 	†
31.	15-BHC (beta)		X	1		-8.	di-n-octvl phthalate*	1	X		-
32.	d-BHC (delta)		X	i	T	79.	4,6-dinitro-2-methyluhenol	• 1	X		†
33.	g-BHC*(gamma)		X	1	1	80.	2,4-dinitrophenol		X		1
34.	bis(2-chloroethyDether"	1	TX	T		31.	2,4-dinitrotoluene		X	-	1
35.	bis2-chloroethoxymethane		X			82.	2,6-dinitrotoluene	1 1	X		T
36.			. 7		;	1 33.	1,2-diphenylhydrazine*		X	·	1
37.	bis(chloromethyl)ether*		╁	1		34.			X	!	
	bis2-ethylhexyllphthalate	1	X			35.	endosulfan II°		X		
59.	bromodichloromethane*	Ī	X	1		36.	endosulfan sulfate		X		
10.	bromoform"		X			87.	lendrin		X		-
11.	bromomethane*	T	X		1	88.			X		T-
42.	4-bromophenylphenyl euer	1	X			: 89.	lethvlhenzene		X		
43.	butylbenzyl phthalate	1	X	1		90.	fluoranthene		X		í
14.	carbon tetrachloride*	1	X			191.	fluorene*		X		
15.	chlordane	1	X	7		92.	heptachlor		X		
	4-chloro-3-methylphenol	-	X	<u> </u>		93.	heptachlor epoxide		X		

SECTION F. PRIORITY POLLUTANT INFORMATION (CON'T)

TTEM NO.	CHEMICAL COMPOUND	SUSPECTED ABSENT	KNOWN	SUSPECTED PRESENT	KNOWN	ITEM NO.	CHEMICAL COMPOUND	SUSPECTED ABSENT	KNOWN	SUSPECTED PRESENT	KNOWN
94.	hexachlorobenzene*		X	<u> </u>		112.	PCB-1248*		X		
95.	hexachlorobutadiene		X			113.	PCB-1254*		X		
96.	hexachlorocyclopenta-		X			114.	PCB-1260*	1	X		
	diene*		X			115.	pentachlorophenol	i	X		
97.	hexachloroethane*		X			116.	phenanthrene	1	X		
98.	indeno(1,2,3-cd)pyrene*		X			117.	phenol		X		
99.	isophorone*		X			118.	pyrene		X		
100.	methylene chloride*		X			119.	2,3,7,8-tetrachlorodi-		X		
101.	naphthalene		X				benzo-p-dioxin*				
102.	nitrobenzene		X_	I		120.	1122-tetrachloroethane*	Ì	X		
103.	2-nitrophenol*		X			121.	tetrachloroethene*		X		
104.	4-nitrouhenol*		X			122.	toluene*	1	X	1	
105.	n-nitrosodimethylamine*		X			123.	toxaphene		X		
106.	n-nitrosodipropylamine*		X			124.	1,2,4-trichlorobenzene	1	X	1	
107.	in-nitrosodiphenylamine*		X			125.	L, L, trichloroethane		X		
108.	PCB-1016*		X			126.	1,1,2-trichloroethane*		X	,	
109.	PCB-1221*		X			127.	trichloroethene*				X
110.	+ PC3-1232*		X		Ī	128.	trichlorofluoromethane		X		
, 111.	PCB-1242*		X			129.	2,4,6-trichlorophenol		X		
	!	1	ĺ			130.	vinyl chloride*	ţ	X	Ţ	1

2. For chemical compounds in F-2 above which are indicated to be "Known Present," please list and provide the following data for each: (attach additional sheets if needed).

ITEM NO.	CHEMICAL COMPOUND	ANNIIAL IISAGE (LBS)	ESTINATED LOSS TO SEWER LRS./YR,	ITEM NO.	CHEMICAL COMPOUND	ANNIAI. IISAGE (LBS)	ESTINATED LOSS TO SEWER LBS./YR.
7	Cadmium (total)	NA	9	; i			
8	Chromium (total)	NA	9		!		
9	Copper (total)	NA	775	į.		1	
10	Lead (total)	NA	53				
12	Nickel (total)	NA	38	ļ		<u> </u>	
16	Zinc (total)	NA 110,000	112			!	<u> </u>
127	Thrichloroethene	110,000	U	<u> </u>	· •	1	<u>'</u>
				-	<u> </u>		
				i i		 	
					i		i
				1			1
				<u> </u>		<u> </u>	!
			<u> </u>	 	1	1	
				-		-	
			 	-		 	-
						 	
		 				1	1
							

	Phosphorus - estimate	ed loss to sewer is	400 lbs/year
		_	
	on process waste stre were sampled, what p	ams in the plant, arameters were mea e baseline report	lyses have been conducte including which stream asured, and frequency an referred to in G2 belo ion.)
	Analysis conducted by	Micon Labs, Warsaw.	Samples have been taken
	at the sampling point	indicated on the at	tached sewer layout on a
	periodic basis. The	following parameters	were measured:
	Ph	Total Cadmium	Total Nickel
	SS	Total Chromium	Total Silver
	Total Cyanide	Total Copper	Total Zinc
	Amenable Cyanide	Total Lead	
_			
3	TION G. PRETREATMENT		
	Te this plant subject	to an existing Pret	reatment Standard?
		· ·	•
	Yes	Ü	
	Yes Is this plant requi 403.12? Yes If a a copy to this quest	red to submit a ba baseline report ha ionnaire. Copy atta ut has not yet been	seline report per 40 CF as been prepared, attac ched If a baseling prepared, indicate dat
	Is this plant requited 403.12? Yes If a a copy to this quest report is required, by that it will be submited. If subject to Feder	red to submit a ba baseline report ha ionnaire. Copy atta ut has not yet been tted. 6/84 al Pretreatment St istent basis? (Th	as been prepared, attac ched If a baselin

4.	Are additional pretreatment facilities and/or operation and maintenance required to meet Pretreatment Standards? If additional pretreatment and/or operation and maintenance are required, list the schedule by which they will be provided. (The baseline report can be referred to in answering this question.)
	Yes. We are currently performing a plant assessment to be
	used to design a waste water treatment system. We have not
	yet finalized our system design and install schedule. We
	intend to be in compliance with the copper forming point source
	requirements by the published August 15, 1986 deadline.
5.	Describe residuals (sludges, precipitates, etc.) that are produced or result at your facility and the methods employed to dispose of the residuals. List names of waste haulers, if applicable.
	Waste Trichloroethylene and sludge/Chemsolv, South Bend
	spent chromic acid solution/A-1 Disposal, Plainwell, MI

